

5     **METHOD OF PHOTOLITHOGRAPHIC EXPOSURE DOSE CONTROL AS A  
FUNCTION OF RESIST SENSITIVITY**

**ABSTRACT OF THE DISCLOSURE**

10    A predictive method is used to compensate for intermediate batch sensitivities which  
inevitably occur during resist batch changeover. The compensation is applied to  
historical dose levels to arrive at a new dose level estimating an optimum dose. When  
the system discovers that a new batch of resist is loaded to a tool, historical data is used  
to calculate a reference dose for each tool. A batch factor is continuously calculated  
15    and using historical data along with the batch factor, a dose adjustment is made to  
maintain proper image size.